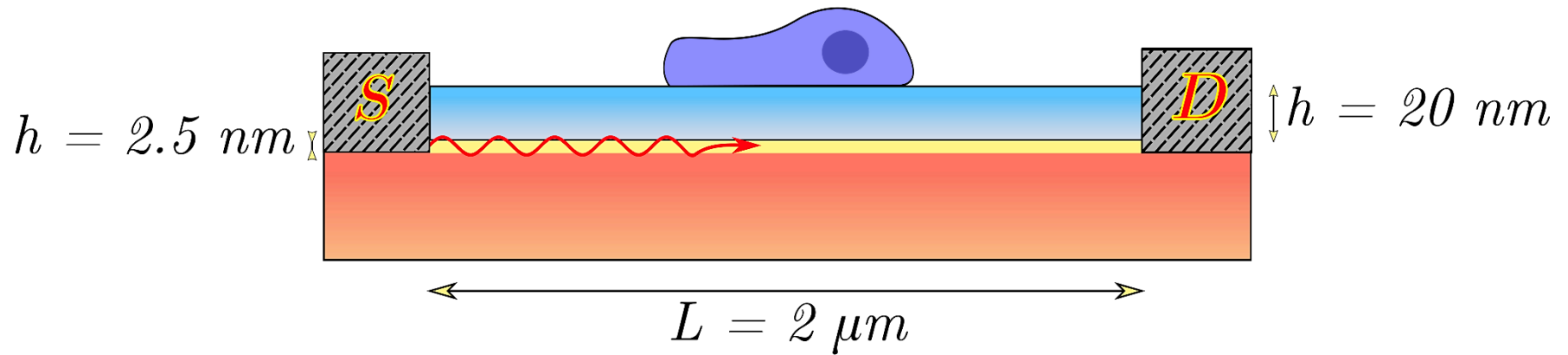


Plasma based High resolution microscopy

4-6-2017

Structure Details



- $\text{Al}_{.2}\text{Ga}_{.8}\text{As}$
- 2DEG
- GaAs

Electrical Properties of 2DEG

- Thin sheet of charge
- Charge density depending on heterostructure materials
- Mobility is temperature dependent

$$N \sim 10^{11} - 10^{14} [\text{cm}^{-2}]$$

$$\mu_{4\text{K}} \sim 10^6 \left[\frac{\text{V}}{\text{cm}^2 \text{s}} \right]$$

$$\mu_{295\text{K}} \sim 10^3 \left[\frac{\text{V}}{\text{cm}^2 \text{s}} \right]$$

$$\tau = \frac{\mu m^*}{e} \propto \frac{1}{T^{1.5}}$$

$$\sigma_s(\omega) = \frac{N e^2 \tau}{m^*} \frac{1}{1 - j \omega \tau} [\text{S}]$$

Dispersion Relation

$$Y_1 + Y_2 + Y_\sigma = 0$$

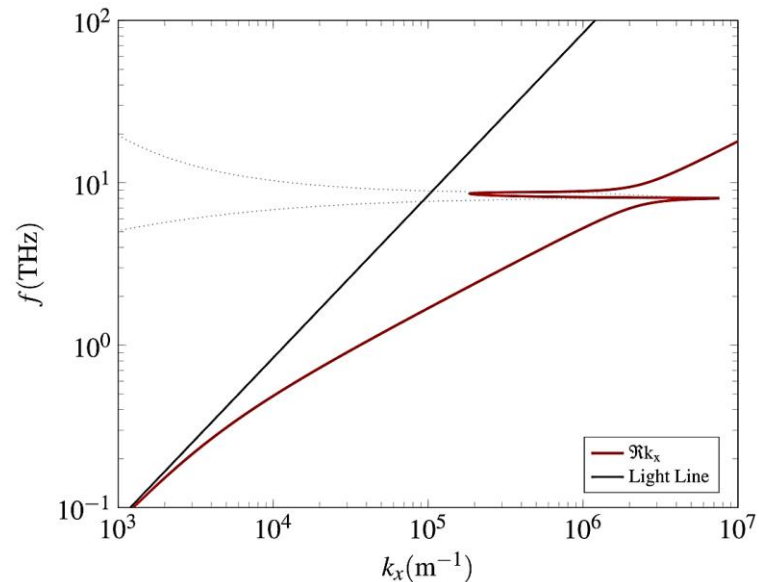
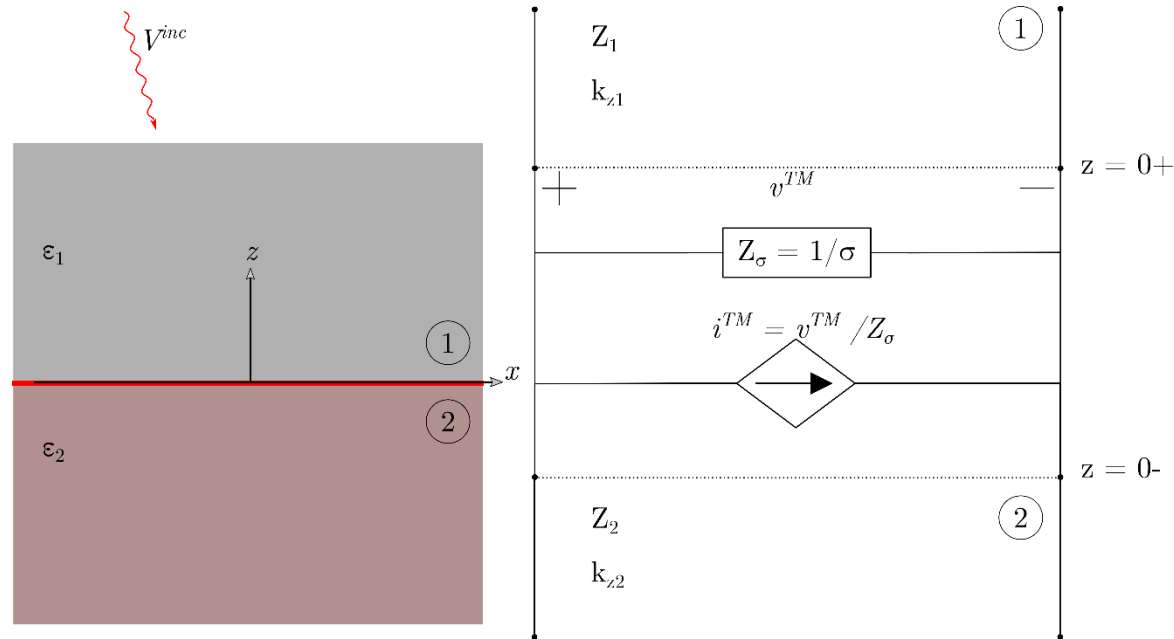
$$\frac{\epsilon_1}{k_{z1}} + \frac{\epsilon_2}{k_{z2}} = -\frac{\sigma_s(\omega)}{\omega \epsilon_0}$$

$$Y_i = \frac{1}{Z_i} = \frac{\omega \epsilon_i}{k_{zi}}$$

$$k_{zi} = \pm \sqrt{\left(\frac{\omega}{c}\right)^2 \epsilon_i - k_x^2}$$

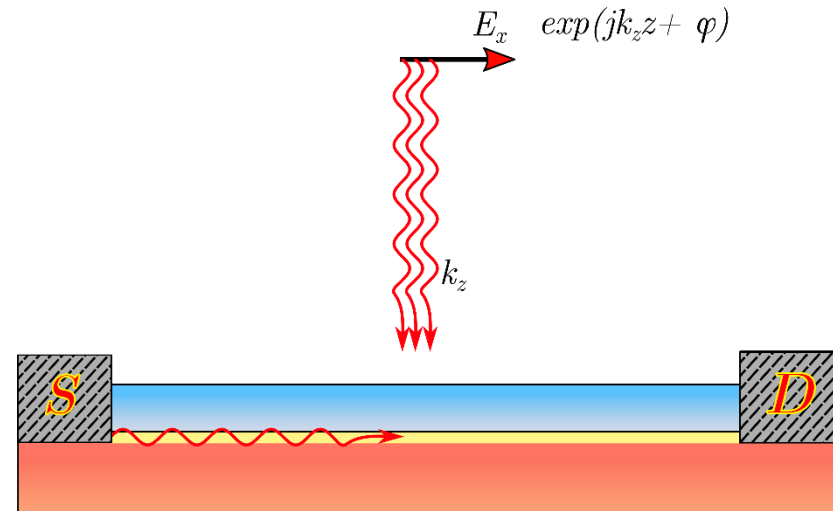
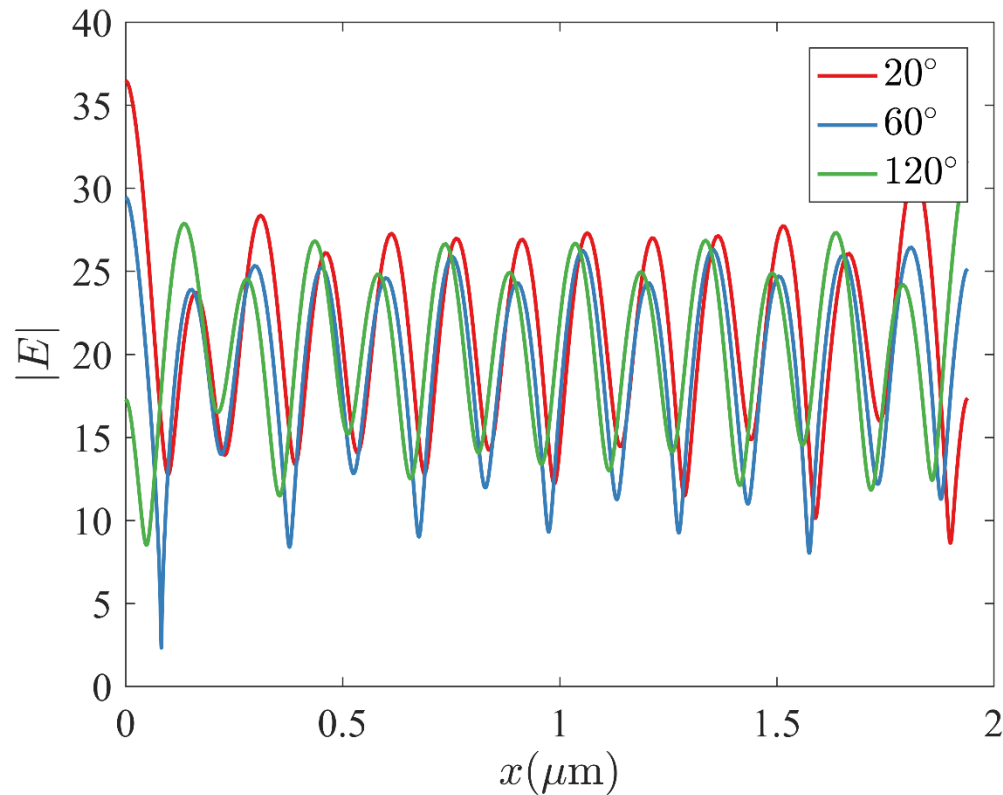
$$Y_\sigma = \frac{1}{Z_\sigma} = \sigma_s$$

$$k_x \approx (\epsilon_1 + \epsilon_2) \frac{\omega}{\sigma_s}$$



Shifting of standing wave

$f = 25 \text{ THZ}$



Standing wave pattern with shifting phase of incident TM wave

COMSOL Simulation

- 2DEG modeled as $d = 2.5$ nm thin slab
 - Surface current used to model surface charge
 - Small negative real part and vanishing imaginary part (close to plasma frequency)

$$\epsilon_{2\text{deg}} = \epsilon_{\text{GaAs}} + j \frac{\sigma_s(\omega)}{\omega d \epsilon_0}$$

- $\epsilon_{\text{GaAs}} = 11$, $\epsilon_{\text{AlGaAs}} = 10.7$

